

## **GaAs and GaN related service**

24/12/2014



# **Measurement capability**

#### Brochure of the daily services

Services	Nb Frequency	Nb Biasing	Nb Transistor	Various Informations	
	1	1	11		
	1	4	3	without contours	
	2	1	4	Without Contours	
Active load pull measurement 1-40GHz (CW)	2	4	1		
Active load pair measurement 1-100112 (OVV)	1	1	6		
	1	3	2	with contours	
	2	1	3	Williamoniours	
	2	2	1		
	1	:::::: <b>::</b>	8		
		4	2	without contours	
	2		3		
Active load pull measurement 1-40GHz (Pulsed)	2	3	1		
route load pair incasarement i routine (i alsea)	1	1	4		
	1	2	2	with contours	
	2	1	2	with contours	
	2	2	1		
Static + Sij (<40GHz) study	-	-	7	complete <sup>1</sup> characterisation	
		1	10	150 to 300 points /	
DC pulsed measurements	**************************************	2	6	quiescent bias point	
		4	4	quiescent olas point	
	-	1	4	150 to 300 points /	
DC + Sij (<40GHz) pulsed measurements	-	2	2	quiescent bias point	
	-	4	1	quiescent bias point	
Design (transistors, amplifier)	contact us				
Non linear modelling	contact us				
Report and reverse engineering	1 day for 4 days of measurements				

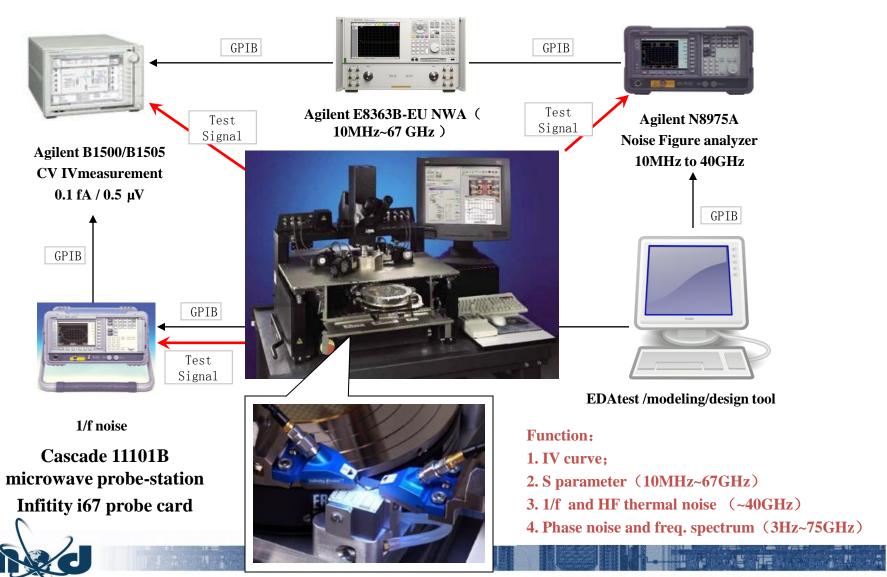
Measurements of diodes in forward and reverse, transconductance, ID(VDS, VGS), ID(VGS, VDS), IG(VDS, VGS), IG(VGS, VDS)

characteristics, access resistance extraction, injection (low total gate width transistors), Sij parameter measurements (6 bias points).

Table is for reference, not updated, if not meets requirement, please contact us

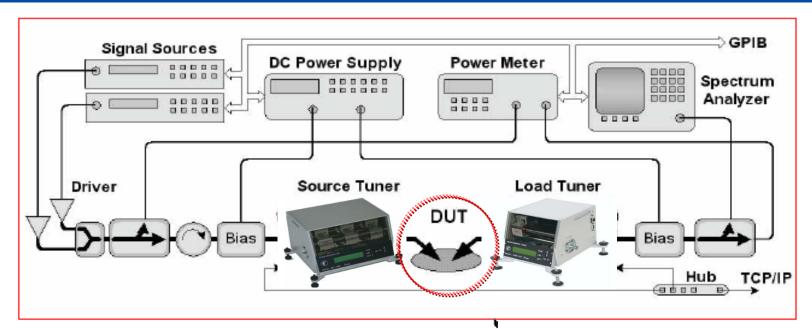


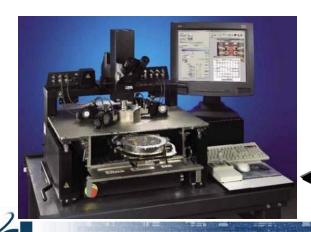
# DC~67GHz On wafer small signal system



**Technologies** 

# 0.8-50GHz Power load-pull system





Technologies

#### **Function:**

- 1. Power device load-pull test
- 2. Harmonic noise matching
- 3.0.8-18GHz, on-wafer test system in LAB1 (China);
- 4.0.8-40GHz, on-wafer test system in LAB2 (France):
- 5. 0.8-50GHz for packaged power device:
- 6. low-high temperature: -60~+200 ℃

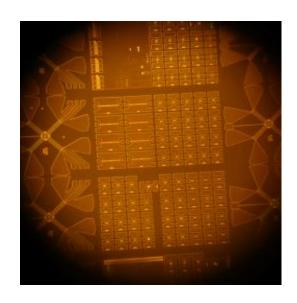
# **III-V Compact Model Development**

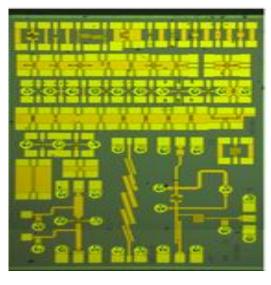
# ☐ GaAs/GaN HEMT modeling

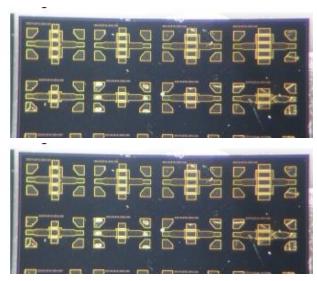
- Agilent EEHEMT, Angelov, Angelov-GaN, Curtice
- Verilog-a based large-signal model

### ☐ GaAs/InP HBT

➤ Agilent HBT, HiCUM, VBIC, GP..







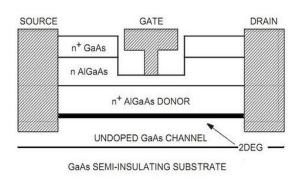
In housed InP HBT

**OMMIC 70nm mHEMT** 

**WIN PP1551 GaAs HEMT** 



# XMOD SP based GaAs\GaN HEMT large-signal model



#### Fig: GaAs HEMT cross section

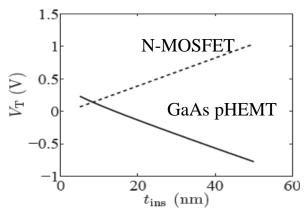


Fig: Inversion and accumulation Vth performance and insulator thickness

### ☐ GaAs\GaN HEMT introduce surface potential

- > Suppose AlGaAs fully depleted
- > 2-DEG as ultra-thin charge sheet
- ➤ bottom layer as insulator
- > neglect impact of hole
- > unconfirmed fact or through flatband voltage correction

### **■** Model equation development method

- ➤ Introduce mathematic function to modify flatband voltage to get correct Vth variation trend
- ➤ Introduce function fine tune bias dependent charge relationship
- ➤ Make use of Si PSP advantage
- □ Solve future GaN E/D HEMT for digital circuits application during simulation
- □ Past WIN foundry test in 2013



# XMOD SP based GaAs\GaN HEMT large-signal model

# ☐ Accurate physical mechanism based model

- ightharpoonup Charge based, SP  $\rightarrow$  I/Q V , suitable for non-linear simulation
- Model is process parameter based, which makes yield targeted model doable
- For mixed signal application, solve GaN digital circuits design related issue

### **□** Better than EEHEMT and OMMIC self built model

> DC. S parameter, wide bias fitting is better than EEHEMT and with HF noise and power simulation result

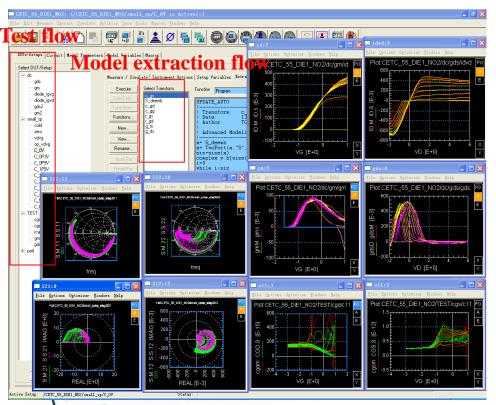
Table Comparison of capabilities between Agilent EEHEMT and XMOD LSP Model.

	Physics Based	Digital Application	Nonlinear Application	I\Q-V High Order Derivable	Charge Conservation	Self Heating	Yield Analysis
EEHEMT1/ 3	×	?	$\sqrt{}$	1	×	X	×
LSP	V	V	V	> 3	V	V	V

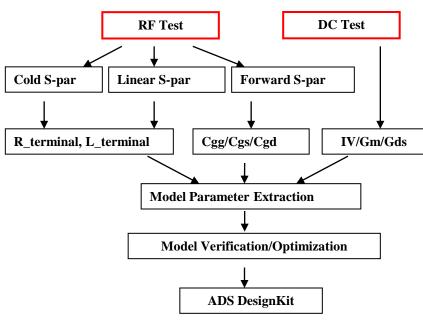


# **Model Extraction Tool Kit Development**

- ☐ Pass GaAs HEMT model evaluation through several partners
- ☐ Agilent IC-CAP based







# Case Show: WIN GaAs HEMT Sample Measurement

# 1. DC/S-parameter test

Device 1 Device 2		Device 3	Device 4	
X5	X5		X5	X5
-55	25		85	
Between 0 and 16 V (16V is BV, careful)				
Between ∀p and 0.6 ∀ (∀p is offstate)				
DC+Sij CW				
	X5 -55 B	-55 Between	X5 X5 -55 2 Between 0 and 16 V (1) Between Vp and 0.6 \	X5   X5   X5

### 2. Pulsed I-V test

Devices	Device 1
Number of samples	X5
Temperature °C	25
Vds0 (V) / Vgs0 (V)	Vds pulsed 0-16V Vgs step 0.1V
Measurement	Pulsed IV



# 3. Power Load-pull test

Devices	Device 1
Number of samples	X1&X5
Temperature °C	25
Frequencies	3 (32,35,38GHz)
Vds0 (V) / Vgs0 (V)	Vds=6V, Vgs at IDS close to static 70mA (dynamic up to 120mA
	limitation) and determined dynamically at the best Pout
Measurement	Loadpull 1 tone (H1 only)

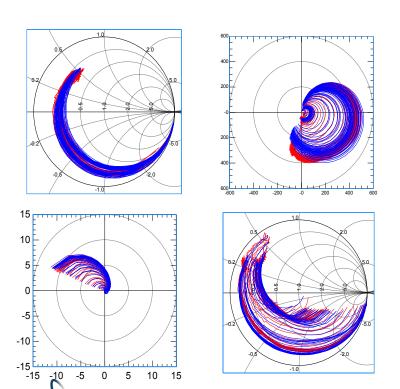
# 4. Noise figure test

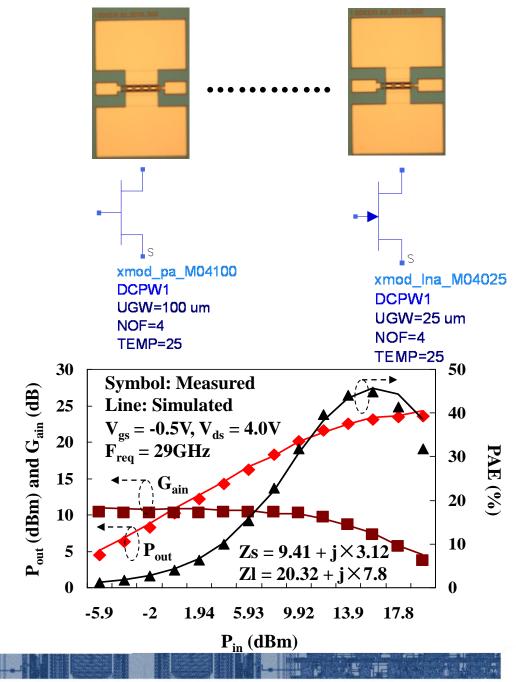
Devices	Device 2	Device 3	Device 4		
Number of samples	X1	X1	X1		
Temperature °C	25				
Vds (V)	1				
Vgs (V)	Between -1.2V and -0.5 (3 bias point)				
Measurement	Noise figure				



# **5. Power Model Lib Development**

- PP1551 Power GaAs HEMT precess
- For mmw T/R chip design
- LSP model for LNA application
- EEHEMT for PA application





# Potential entry points of XMOD & Customer

□ Golden device to debug test equipment set up
 □ Testkey layout design or audit
 □ Measurement outsourcing
 □ Modeling outsourcing (including reliability model in Wafer or Package level)
 □ Design house or foundry consulting
 □ On-site training or training course for customers









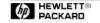
Dr. Franz Sischka studied communication engineering at the University of Stuttgart, Germany, where he received his Diplom-Ingenieur and Ph.D. degrees in 1979 and 1984. He joined Hewlett-Packard in Boeblingen/Germany, working in R&D in the fiber optics group. Since 1989, he became a consultant for Hewlett-Packard's, later Agilent-EEsof's device modeling software IC-CAP. During that time, he has focused on developing strategies for verified, reliable device measurements and also worked on modeling strategies for diodes, bipolar and GaAs transistors, as well as for passive components like spiral inductors, varactors etc.

Technologies

#### **IC-CAP Modeling Reference**

Measurement, Modeling and Simulation of Electronic Components and Circuits

> May 1999 HP Part No. 85190-90088



Book author: Dr. Franz Sischka is consultant of XMOD and will come to shanghai in June 2015 to hold 2 days training course and deliver on-site training or consulting for company

# **Course Topics**

### **Main detailed topics:**

- 1. Measurements
- 2. Measurement Data Quality Verification
- 3. Selecting a Model (Simulation)
- 4. Performing the Modeling

#### MEASUREMENT RELATED

- Standardized Data Formats For Electronic Device Measurements
- Chapters about DC, CV, S-Parameter, Nonlinear-RF and 1/f Noise

### DATA QUALITY VERIFICATION RELATED\_

- Chapters about DC, CV and S-Parameter verifications
- Nonlinear Network Analyzer Data Verification

### Keywords:

Nonlinear Vector Network Analyzer (NVNA), DC Biasing Verification, NVNA Calibration



#### **SIMULATION RELATED**

• How to Simulate Pulsed DC Curves Keywords:

Pulsed DC Measurements, Device Self-Heating, Simulating Pulsed DC curves, Thermal Node of Transistor Models

How to Simulate CV Curves

Keywords:

CV Measurement Principle, Simulating CV Curves, Interpretation of the Simulated Impedance, CV Simulations for Devices with >2 Pins

How to Simulate S-Parameters

Keywords:

S-Parameter Measurement Principle, S-Parameters from AC Simulations, DC Biasing, Influence of Bias-TEEs, Noisy or Discontinuous S-Parameter Simulation

● How to Simulate 1/f Noise

Keywords:

FET and Bipolar Noise Sources and Models, Measurement-Related 1/f Noise Simulations, Bipolar Noise Affected by DC Bias Resistance



#### **MODELING RELATED**

Modeling Methods: Line Fitting

Keywords:

Fitting a Line to Measurement Data, Regression Analysis, Linear Fit, Capacitance CV Fit, S-Parameter Fit, Diode Example

Modeling Methods: Visual Parameter Extraction

Keywords:

Converting measurements into model parameter plots, verification of model equation validity

Modeling Methods: Subcircuit Modeling

Keywords:

Fitting device measurements by using subcircuits composed of standard models

Modeling Methods: Transistor PI Schematic Modeling

Keywords:

Description of how to convert S-Parameters of FET or HEMT Transistors to Inner PI Schematic Modeling and Parameter Extraction

Equations for MultiPort Matrix Conversions

Keywords:

Z-Parameter, Y-Parameter, S-Parameter, Matrix Conversion, N-Port, Matrix Signal Flows

